

Docket No.: MUH-12818



IPW

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the date indicated below:

By:

Date: July 22, 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applic. No. : 10/675,049 Confirmation No: 5871
Applicant : Ioannis Dotsikas
Filed : September 30, 2003
Title : Method and Furnace for the Vapor Phase Deposition of
Components onto Semiconductor Substrates with a Variable
Main Flow Direction of the Process Gas
Art Unit : 2818
Examiner : Renee R. Berry
Docket No. : MUH-12818
Customer No. : 24131

R E S P O N S E

Hon. Commissioner for Patents

S i r:

Responsive to the Office Action dated June 30, 2004, the following remarks are made:

In deference to the restriction requirement on pages 2 and 3 of the above-identified Office Action, applicant elects group II, claims 13-17, for prosecution at this time.

Applicant requests a rejoinder under MPEP §821.04.

In view of the foregoing, the early issuance of an Action on the merits of claims 13-17 is solicited.

Respectfully submitted,

For Applicant

Date: July 22, 2004

WERNER H. STEMER
REG. NO. 34,956

Lerner and Greenberg, P.A.
Post Office Box 2480
Hollywood, FL 33022-2480
Tel: (954) 925-1100
Fax: (954) 925-1101
/bmb